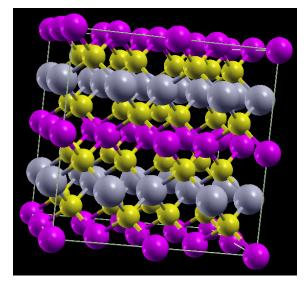
Clancy group: 2015 M.Eng. projects– Electronic materials

1. Next Generation Semiconductor Design- Doped III-V materials.



Purple, green, grey: Alternating layers of In, Ga, As

Electrons in Electrons out
Metal contact
Sate
Thin-film semiconductor voltage
Source $\Rightarrow \Rightarrow \Rightarrow \Rightarrow$ Drain
Insulator
Gate
Substrate

Background

- Further improvement in Si-based logic devices is limited.
- Recapture "Moore's law" with ternary III/V materials (In_{0.47}Ga_{0.53} As) with Si as a dopant
- Collaboration with Thompson and industry
 - M.Eng. Project: Study diffusion of dopant atoms (Si) in InGaAs

Computational Tools:

- Electronic structure calculations
 - Molecular Dynamics
 - Kinetic Monte Carlo